

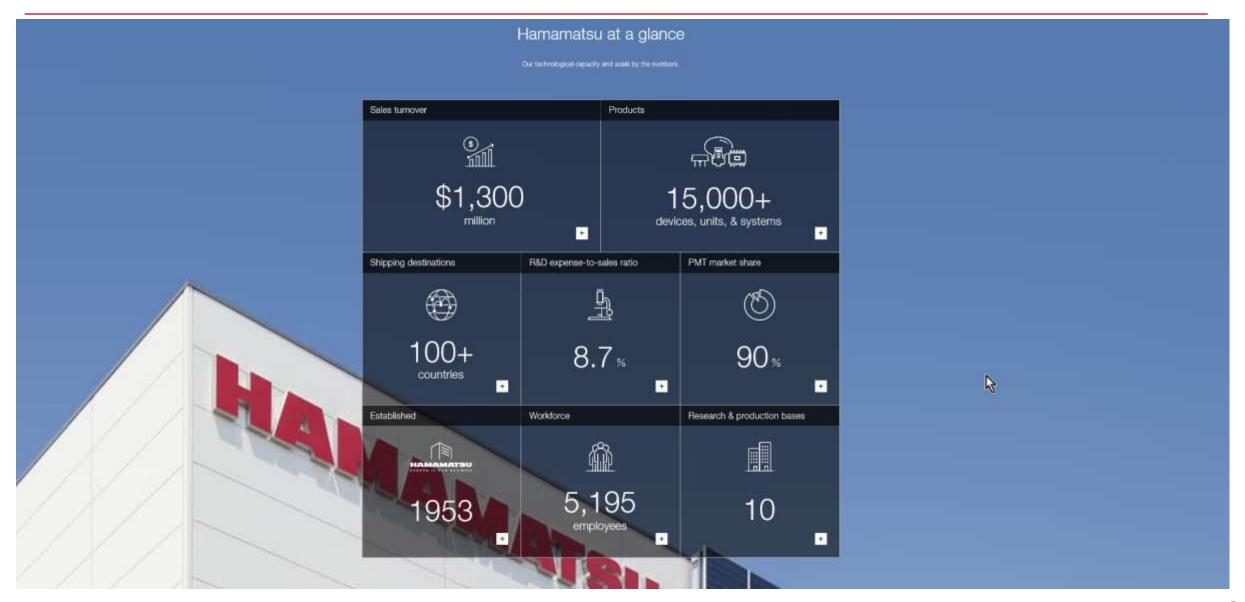
PIC Monolithic vs Hybrid

Marco Mayer Hamamatsu Photonics June 10th, 2021

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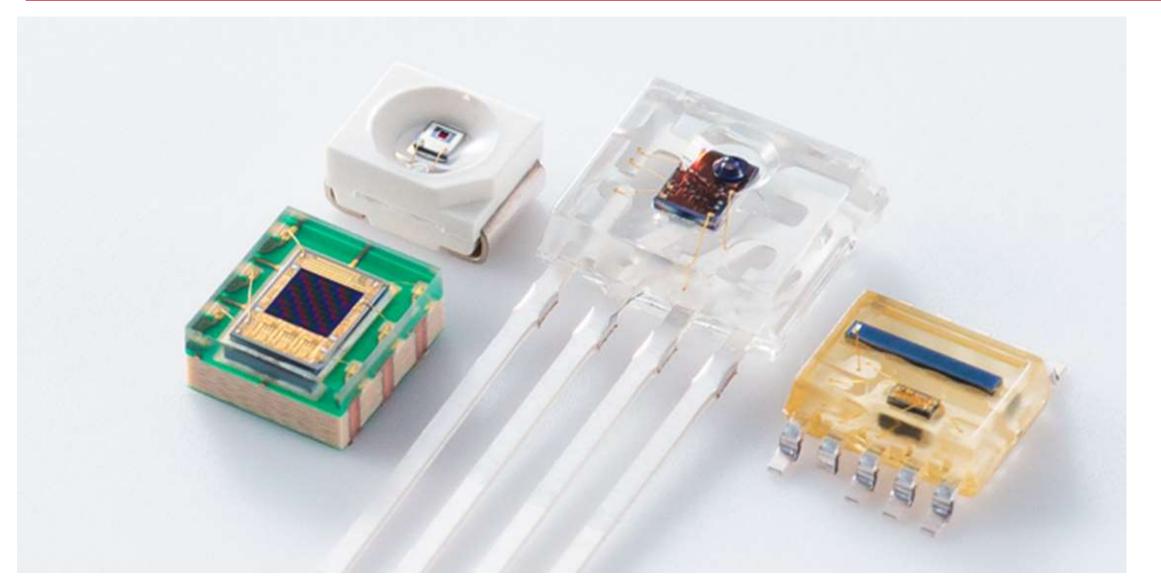
Introduction





PIC by Hamamatsu





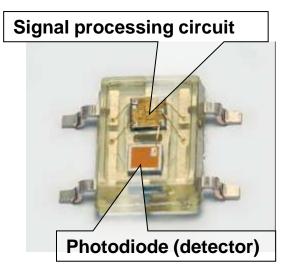


Configuration

Classification of Photo IC

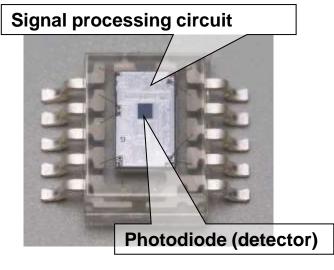
 \rightarrow Construction : Hybrid type & Monolithic type





2 chip on one package

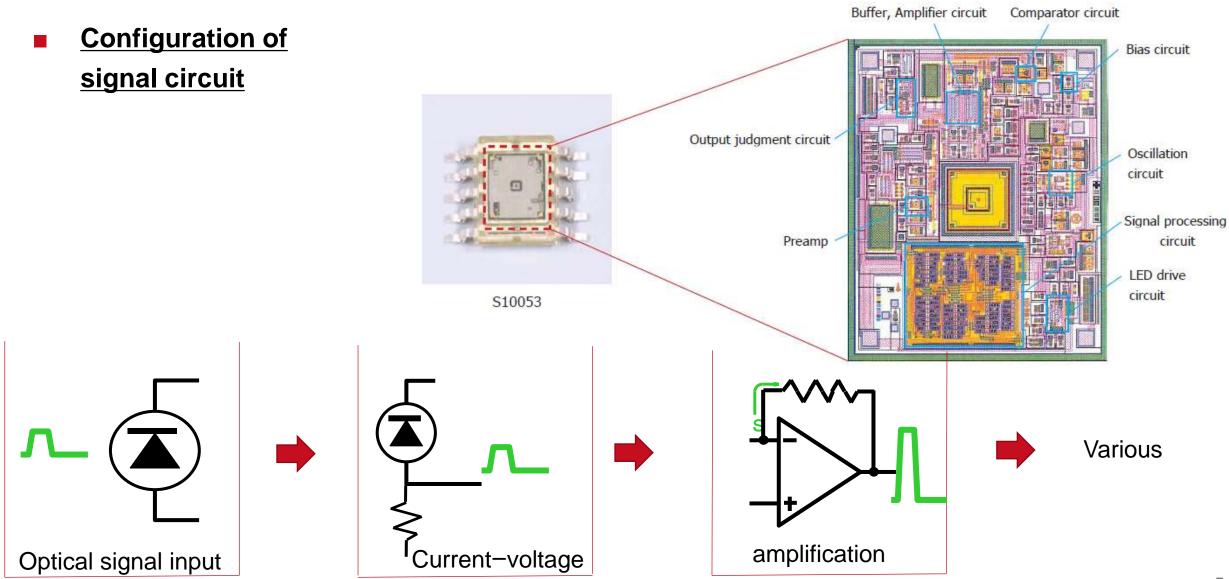
Monolithic type Photo IC



One chip on one package

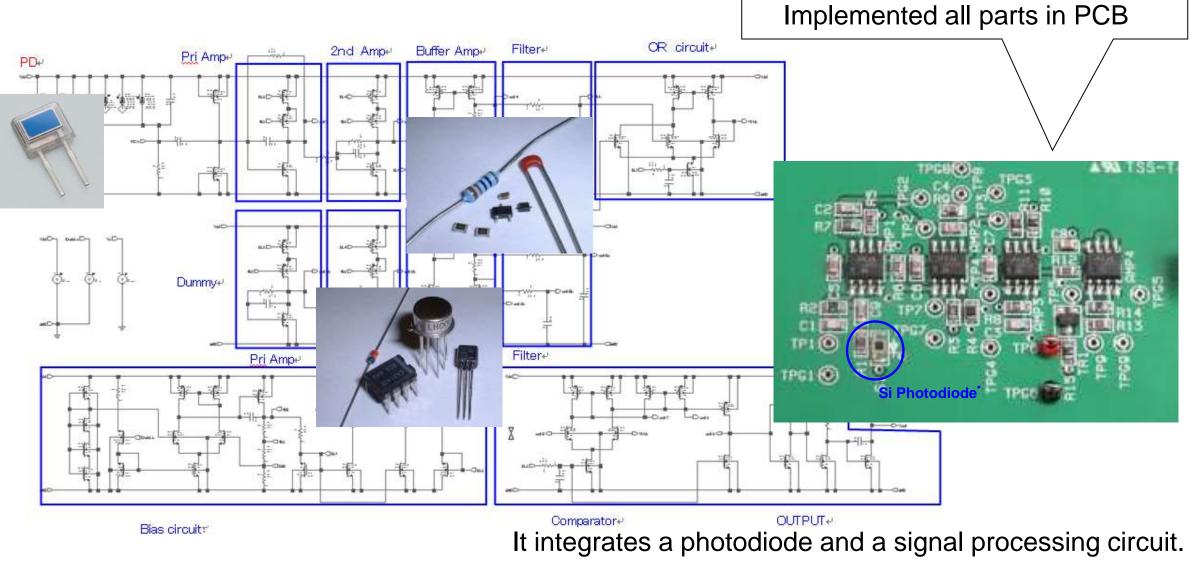
What is a Photo IC

HAMAMATSU PHOTON IS OUR BUSINESS



What is Photo IC

FOR INTERNAL USE ONLY



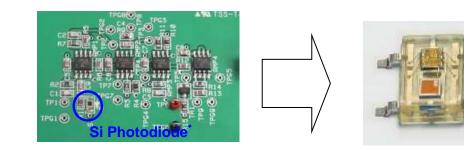
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6

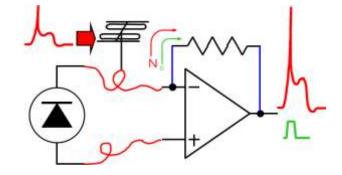
Low Cost Small Size Light weight Low noise

> Main feature

Low cost Small size Light weight

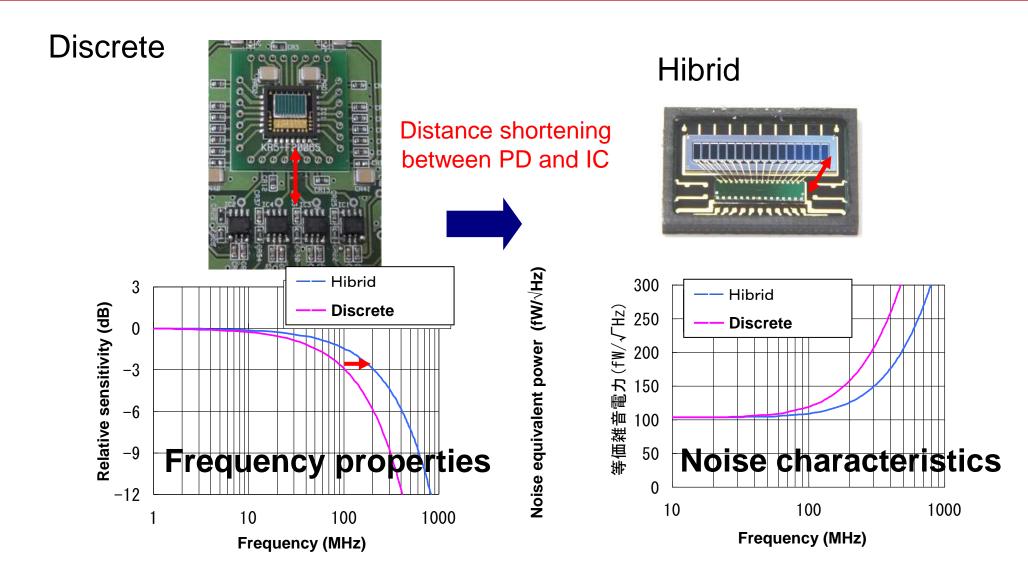


Advantage
Low noise



The explanation of Photo IC (Noise example)

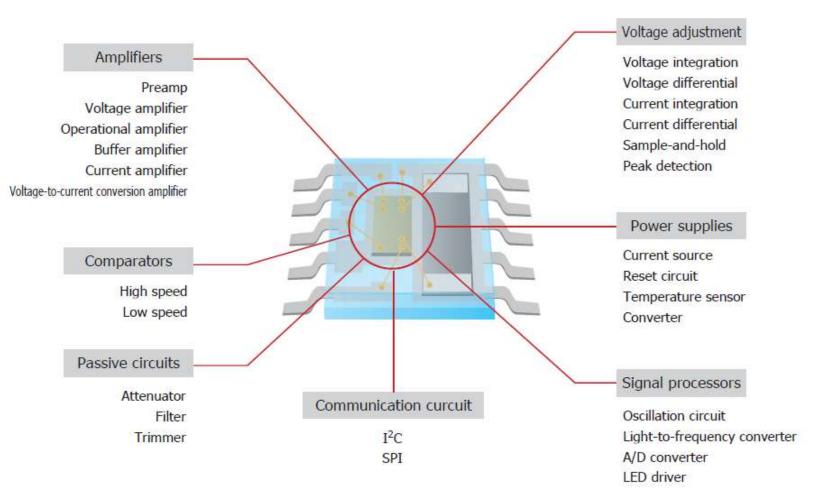
FOR INTERNAL USE ONLY



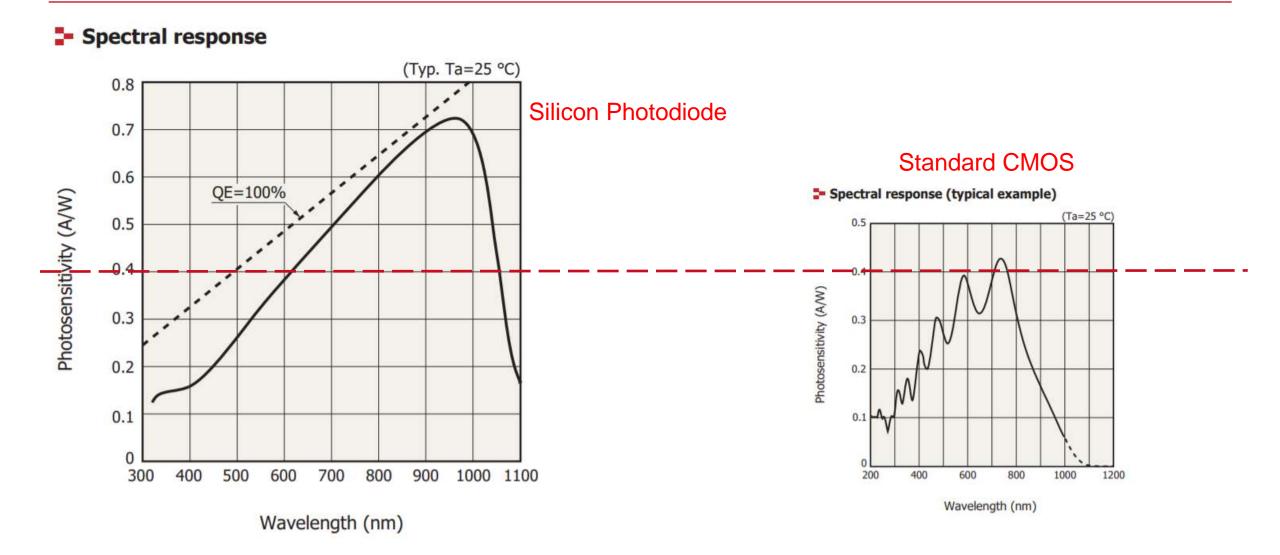
Circuit technology for Photo IC



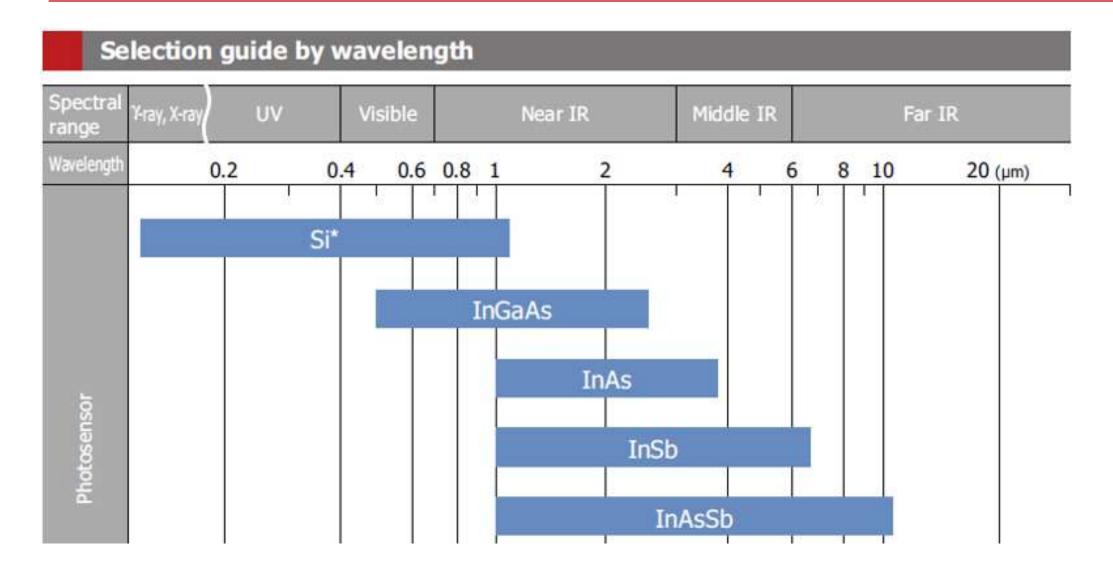
Hamamatsu has analog circuit library so that it can contribute to quicker development and lower developmental cost.

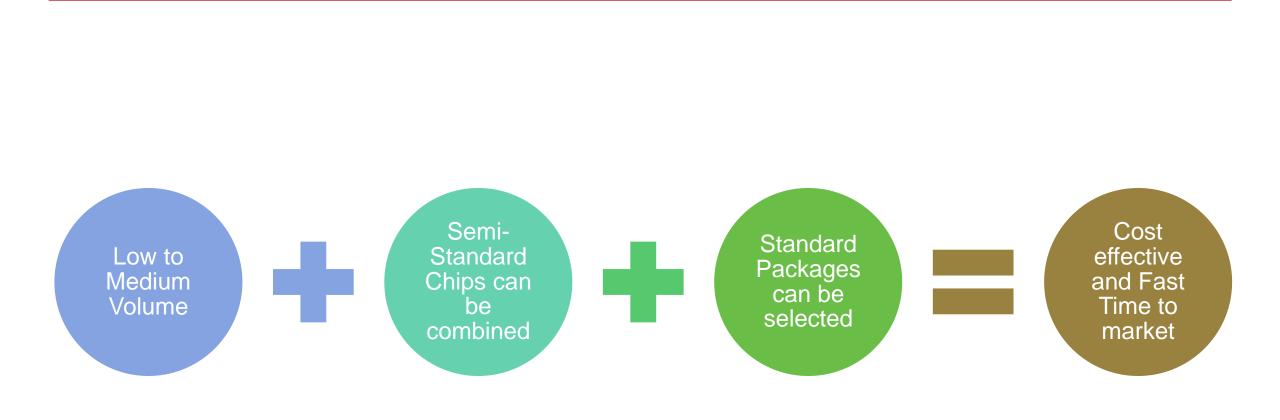


Why now separate the detector and the Circuit? Different Processes









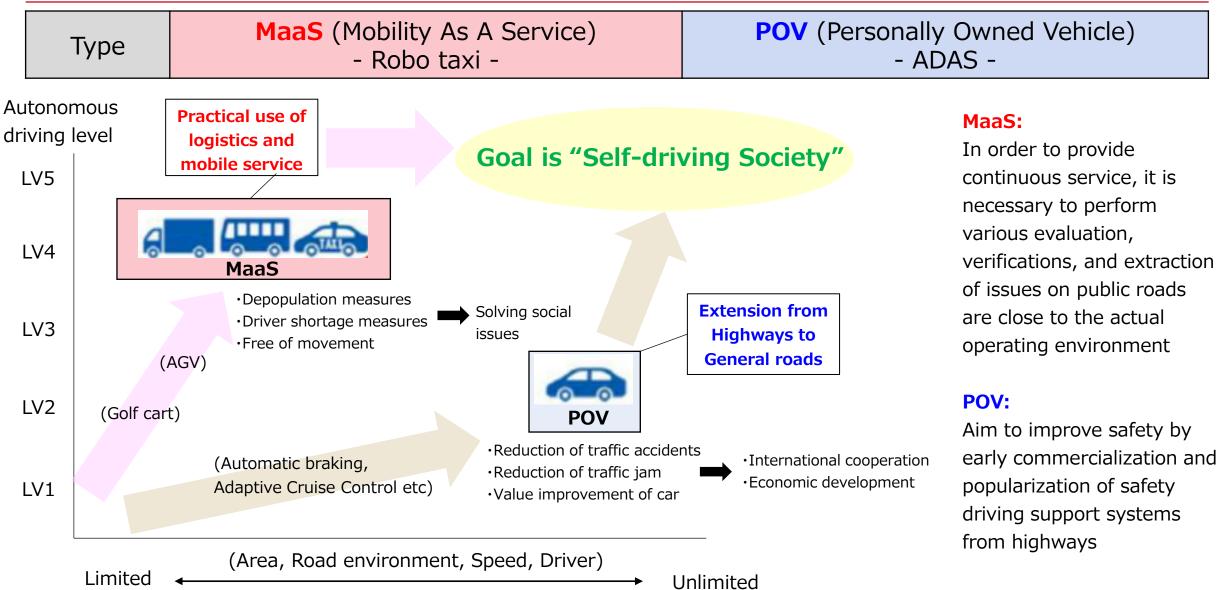
HAMAM



Application example / LiDAR

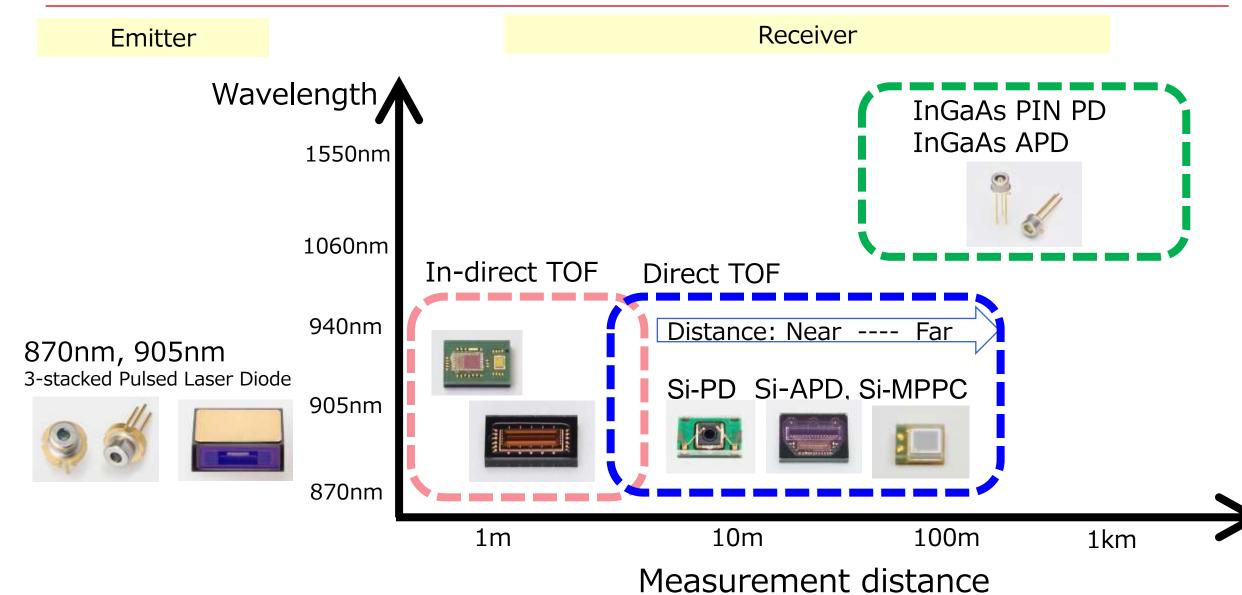
Category of future's mobility





Lineup from wavelength and measurement distance

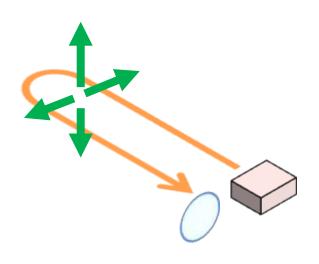




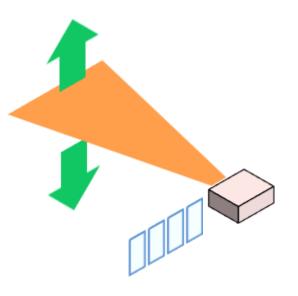
Receiver shape required for LiDAR



Point light + 2D scanner + Single detector

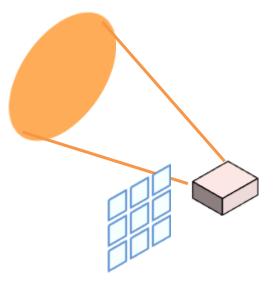


Fan beam + 1D scanner + 1D array detector





+ 2D array detector



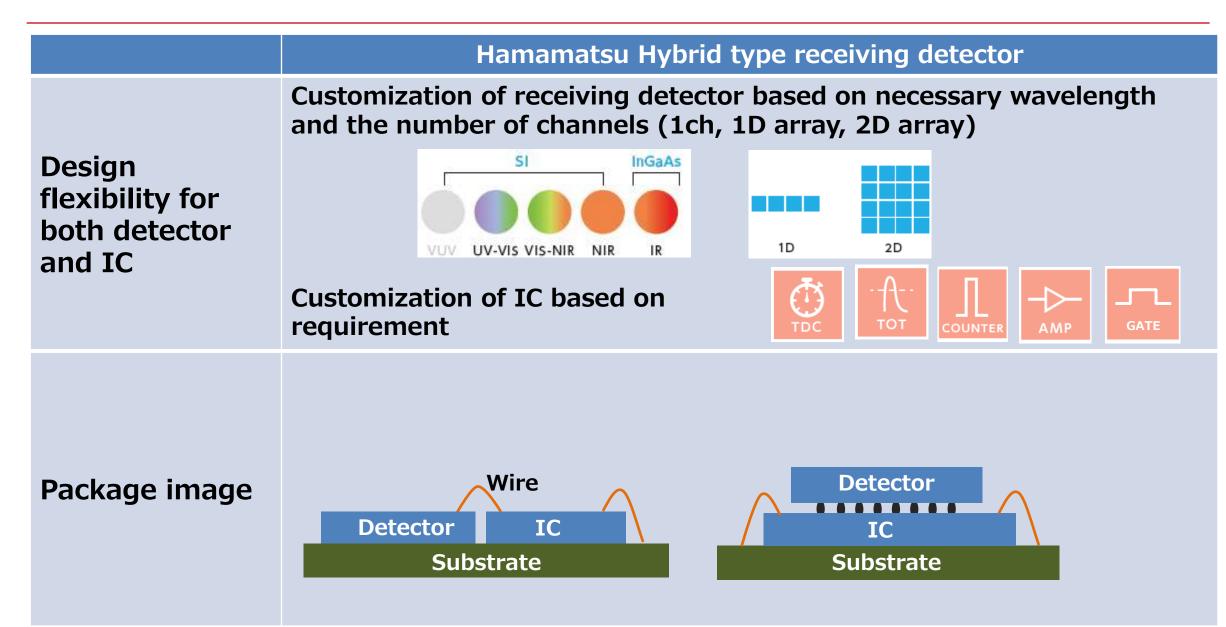
<u>Mainly for long range</u> (Module size tends to bigger because scan mechanism is necessary)



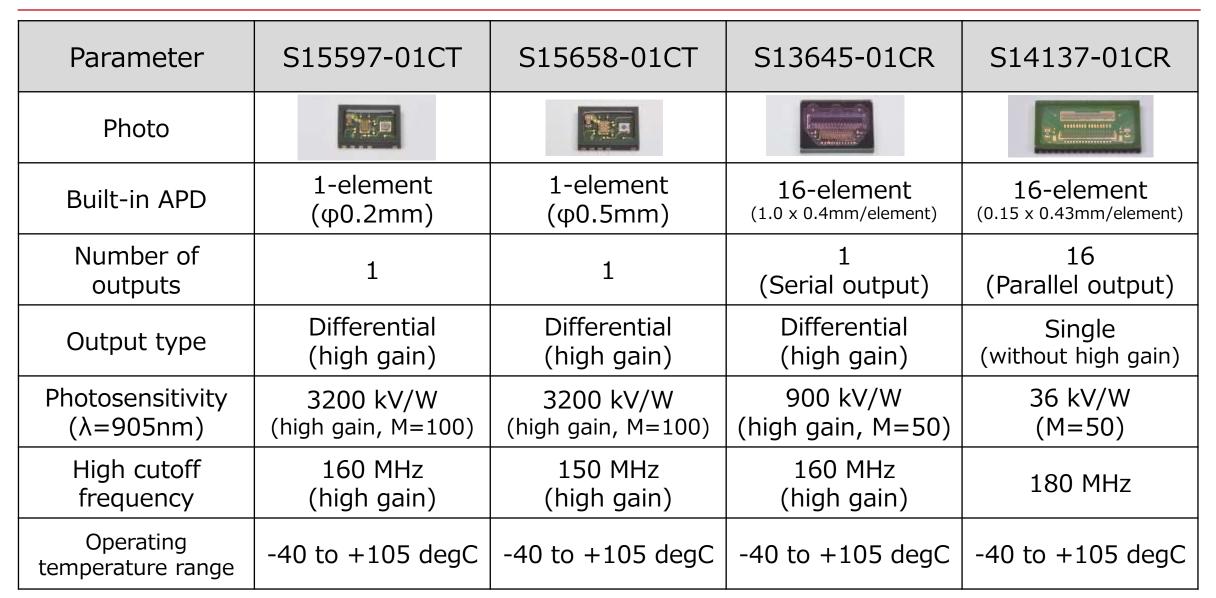
<u>Mainly for short range</u> (Easier to minimize because scanner is not necessary. High sensitivity 2D detector is necessary)

Hybrid type Receiving detector with IC





Lineup of Si APD+IC (TIA) Hybrid type



Lineup of InGaAs APD+IC (TIA) Hybrid type

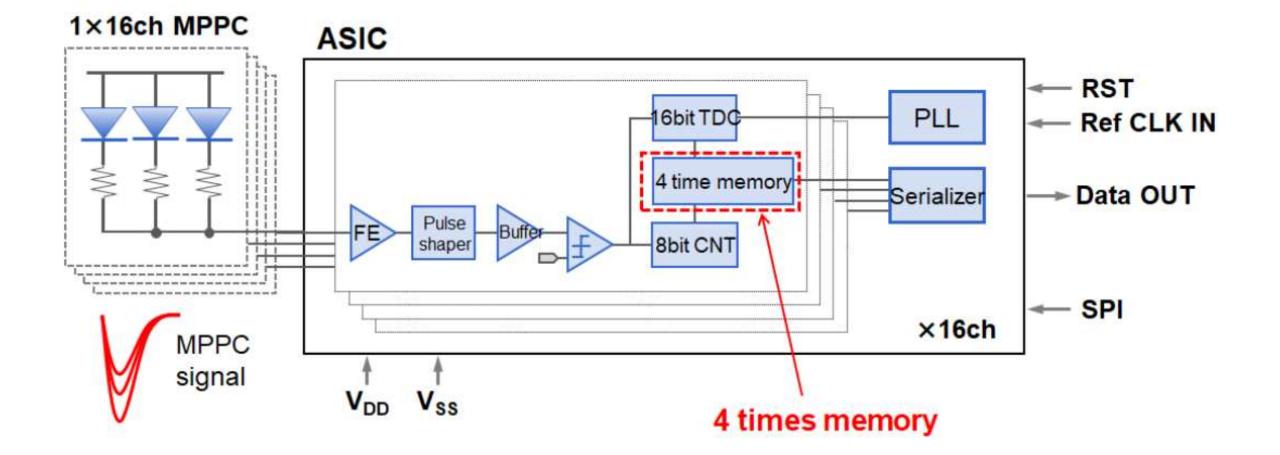
| Parameter | G15749 UNDER DEVELOPMENT | G15799 UNDER DEVELOPMENT |
|---|-----------------------------|---------------------------------------|
| Photo | | |
| Built-in InGaAs APD | 1-element (φ0.2mm) | 16-element (0.15 x 0.43mm/element) |
| Number of outputs | 1 | 16 (Parallel output) |
| TIA gain AC(0.1uF) + 50ohm load | 0.8kV/A | 0.8kV/A |
| Higher cutoff frequency AC(0.1uF) + 50ohm load | 270MHz | 200MHz |
| Operating temperature range | -40 to +105 degC | -40 to +105 degC |

Photoncounting array with IC Hybrid type to our management of the second second

| Parameter | S15022-0225GL-01 | S15013-0125NP-01 UNDER DEVELOPMENT |
|--------------------|--|--|
| Photo | | |
| Built-in MPPC | 16ch front illuminated type MPPC (200x200um/Channel) | 32 x 32ch back-illuminated type MPPC (100x100um/Channel) |
| Number of pixel/Ch | 64ch | 12ch |
| Pixel pitch | 25um | 25um |
| PDE at 905nm | 9% | 6% |
| Features | Integrated TDC (Time-to-Digital Converter) 4 times Multi-echo detection per measurement | 2D array with ASIC connected by Solder Bumps Integrated TDC (Time-to-Digital Converter) on each pixel |

Block diagram of S15022-0225GL-01







Application example / Optical encoder

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Monolithic Photo IC for Reflective encoder

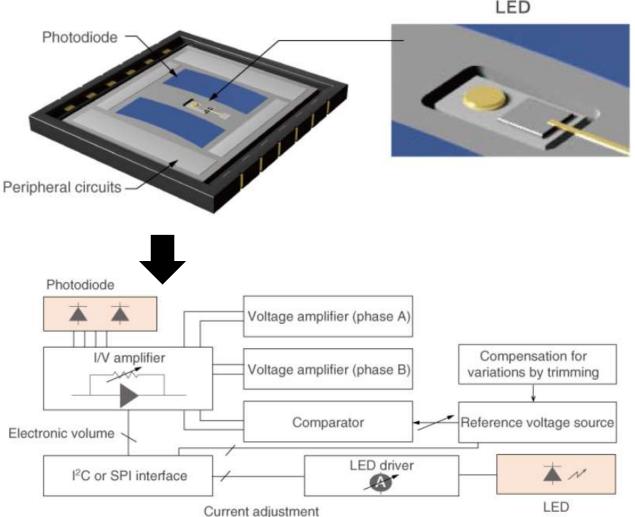
Photo IC Photodiode and LED are integrated with Peripheral circuits

Features

Monolithic structure of PD and peripheral circuit

 \Rightarrow Helps reduce the number of parts and mounting space on the customer side

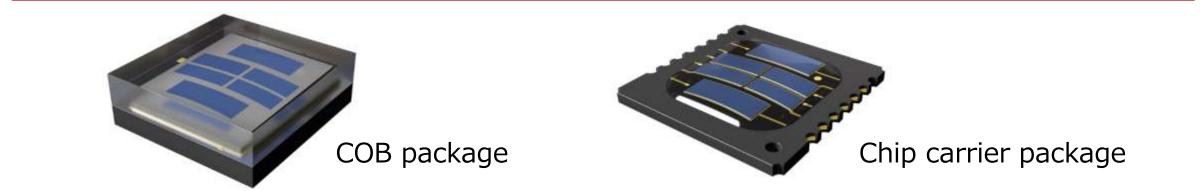
- Multi-functionalization using I2C \Rightarrow Enables multi-functionalization such as electron volume
- Built-in LED and LED driver \Rightarrow Photo IC including receiver and emitter with LED placed in the center of the chip
- Compensation for variations in reference values (current, voltage) by trimming

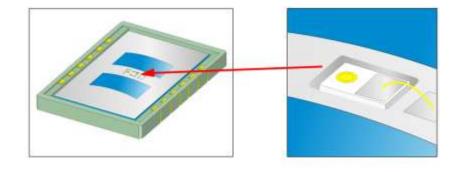






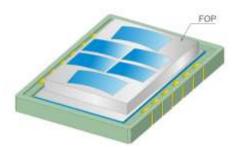
Package proposal for Encoder application



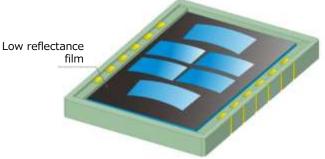


MEMS processing

In order to align the height between LED chip mounted in the center hole and PD chip, thickness of PD can be adjusted by the MEMS processing.



FOP (Fiber Optic Plate) Combining the FOP with PD, focus of lens at the position where is thicker than PD active area surface is possible.



Low reflectance film Due to lower reflectance at PD chip surface and metal wirings, it can contribute to better S/N.

Ichino factory For wafer process like PD, APD, and CMOS





Miyakoda factory For compound semiconductor process





Shingai factory For assembly process for high volume products







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